제 30회 한국반도체학술대회

The 30th Korean Conference on Semiconductors

2023년 2월 13일(월)~ 15일(수) | 강원도 하이원리조트(그랜드호텔 컨벤션타워)

2023년 2월 15일(수), 16:00-17:45
Room B (에메랄드 II+III, 5층)

D. Thin Film Process Technology 분과

[WB3-D] Area-selective Deposition

좌장: 김우희 교수(한양대학교), 오일권 교수(아주대학교)

WB3-D-1 **16:00-16:30** **[초청]**	**Precursor Choice of Metal Oxides in Atomic Layer Deposition** Il-Kwon Oh *Department of Electrical and Computer Engineering, Ajou University*
WB3-D-2 **16:30-16:45**	**Selective Etching Reactions during Atomic Layer Deposition of Indium Gallium Zinc Oxide** Iaan Cho[1], Jae Hoon Cho[2], Jae Kyeong Jeong[2], and Bonggeun Shong[1] *[1]Department of Chemical Engineering, Hongik University, [2]Department of Electronic Engineering, Hanyang University*
WB3-D-3 **16:45-17:00**	**Area Selective Deposition Using Ruthenium Precursor Inhibitor and Control of Inhibitor Packing Density** Chi Thang Nguyen[1], Eun-Hyoung Cho[2], Ngoc Le Trinh[1], Bonwook Gu[1], Mingyu Lee[1], and Han-Bo-Ram Lee[1] *[1]Department of Materials Science and Engineering, Incheon National University, [2]Beyond Silicon Lab, Samsung Advanced Institute of Technology*
WB3-D-4 **17:00-17:15**	**Area-Selective Atomic Layer Deposition of Ru Thin Films Using Aldehyde-Based Inhibitors on Nitride Surfaces** Jinseon Lee and Woo-Hee Kim *Department of Materials Science and Chemical Engineering, Hanyang University*
WB3-D-5 **17:15-17:30**	**Demonstrations on Synaptic Operations of In-Ga-Zn-O Thin Film Transistor Using Solution-Process Li-doped ZrO_2 Electrolyte Gate Insulator** Dong-Hee Kim[1], Young-Ha Kwon[2], Nak-Jin Seong[2], Kyu-Jeong Choi[2], and Sung-Min Yoon[1] *[1]Kyung Hee University, [2]NCD Co., Ltd.*
WB3-D-6 **17:30-17:45**	**Thiol Instigated Area Selective Deposition of HfO_2 ALD on Copper, Silicon Oxide and Titanium Nitride Substrates** Summal Zoha[1], Bonwook Gu[1], Zunair Masroor[1], Fabian Pieck[2], Ralf Tonner[2], and Han-Bo-Ram Lee[1] *[1]Department of Materials Science and Engineering, Incheon National University, [2]Wilhelm Ostwald Institute for Physical and Theoretical Chemistry, University of Leipzig*